

ACKNOWLEDGEMENT RECEIPT

Electronic Version 1.1

Stylesheet Version v1.1.1

Title of Invention

Method for forming silicon dioxide film using siloxane

Submission Type : Information Disclosure
Statement

Application Number:

10/782094



EFS ID:

87192

Server Response:

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First Named Applicant: Jae-eun Park

Attorney Docket Number: SAM-0483

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File Listing:

Doc. Name	File Name	Size (Bytes)	Date Produced (yyyymmdd)
us-ids	SamsungFourEightyThreePartThree-usidst.xml	945	2005-06-28
us-ids	us-ids.dtd	7763	2005-06-28
us-ids	us-ids.xsl	12026	2005-06-28
package-data	SamsungFourEightyThreePartThree-pkdata.xml	2056	2005-06-28
package-data	package-data.dtd	27025	2005-06-28
package-data	us-package-data.xsl	19263	2005-06-28
Total files size		69078	

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